

WHAT IS CLAIMED IS:

1. Resist stripping equipment, comprising:

a resist stripping chamber in which a substrate covered with resist is accommodated and resist stripping solution is supplied onto the substrate;

a gas/liquid separation block which is connected to the resist stripping chamber, and to which mixed gas containing a resist stripping solution component in the resist stripping chamber is introduced, and in which the resist stripping solution component of the mixed gas is separated; and

a recovered resist stripping solution supply block which is connected to the gas/liquid separation block and supplies the separated resist stripping solution component to the resist stripping chamber.

2. The resist stripping equipment of claim 1, further comprising:

a separated gas supply unit which receives gas separated from the resist stripping solution component in the liquid/gas separation block and supplies the gas to the gas spout unit,

wherein the resist stripping chamber includes a gas spout unit.

3. The resist stripping equipment of claim 2, wherein the gas spout unit is disposed facing the substrate.

4. The resist stripping equipment of claim 1,
further comprising:

an inert gas supply unit which is connected to the
resist stripping chamber and supplies inert gas into
5 the resist stripping chamber.

5. The resist stripping equipment of claim 4,
comprising:

a plurality of the resist stripping chambers
provided in multiple stages to communicate with each
10 other;

a rinse chamber provided to communicate with one
of the plurality of resist stripping chambers at a last
stage, the rinse chamber being supplied with water;

the gas/liquid separation block connected to one
15 of the plurality of resist stripping chambers at a
first stage; and

the inert gas supply unit connected to the rinse
chamber,

wherein the resist stripping solution is water-
20 based resist stripping solution.

6. The resist stripping equipment of claim 4,
comprising:

a plurality of the resist stripping chambers
provided in multiple stages to communicate with each
25 other;

a rinse chamber provided to communicate with one

of the plurality of resist stripping chambers at a last stage, the rinse chamber being supplied with water;

the gas/liquid separation block connected to one of the plurality of resist stripping chambers at a
5 first stage; and

the inert gas supply unit connected to one of the plurality of resist stripping chambers at the last stage,

wherein the resist stripping solution is non-
10 water-based resist stripping solution.